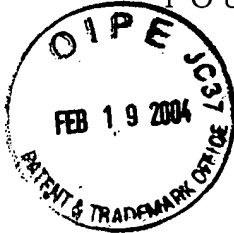


GEORGE O. SAILE & ASSOCIATES
28 DAVIS AVENUE
POUGHKEEPSIE, NY 12603

TS03-065



February 9, 2004

To: Mail Stop Application Number
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

From: Stephen B. Ackerman

Subject: Serial No.: 10/688,045
Filing Date: 10/17/2003
Inventor: H. J. Lin, et al
Title: Fully Dry, Si Recess Free Process for Removing High k
Dielectric Layer

REQUEST TO CORRECT FILING RECEIPT

Dear Sir:

On the copy of the enclosed Filing Receipt, there are errors in the list of Applicants. The third Applicant's name is misspelled. Mr. Lin's corrected name and residence reads; **Li-Te S. Lin, Hsin-Chu, Taiwan**. The fourth Applicant's residence is misspelled. Mr. Chiu's name and corrected residence reads; **Yuan-Hung Chiu, Taipei, Taiwan**.

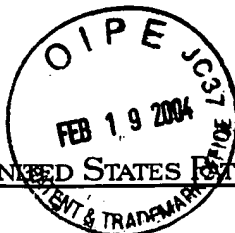
Please make the necessary changes to correct the errors on the Filing Receipt.

If there are any questions, please contact the undersigned attorney at (845) 452-5863. Thank you for your attention to this matter.

Respectfully Submitted,

Stephen B. Ackerman, Reg. No. 37,761

FEB. 08 2004



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APPL NO.	FILING OR 371 (c) DATE	ART. UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/688,045	10/17/2003	1765	1130	TS03-065	3	40	2

CONFIRMATION NO. 9213

STEPHEN B. ACKERMAN
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FILING RECEIPT



OC000000011825952

Date Mailed: 02/04/2004

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Filing Receipt Corrections, facsimile number 703-746-9195. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Huan-Just Lin, Hsin-Chu, TAIWAN;
 Ming-Huan Tsai, Hsinchu, TAIWAN;
 Li-Tes Lin, Hsin-Chu, TAIWAN;
 Yuan-Hung Chiu, Taipei, TAIWAN;
 Han-Jan Tao, Hsinchu, TAIWAN;

Li-Tes Lin

Assignment For Published Patent Application

Taiwan Semiconductor Manufacturing Co.;

Domestic Priority data as claimed by applicant

Foreign Applications

If Required, Foreign Filing License Granted: 02/03/2004

Projected Publication Date: 04/21/2005

Non-Publication Request: No

Early Publication Request: No

Title

Fully dry, Si recess free process for removing high k dielectric layer

Preliminary Class

117

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